

WHAT IS CLAIMED IS:

1. A process for producing a mesostructured thin film having an oriented rod-like pore structure, comprising the step of forming the mesostructured thin film on a polymer compound containing a sequence of two or more adjacent methylene groups in a molecular structure of the repeating unit of the polymer compound.
2. The process for producing a mesostructured thin film according to claim 1, wherein the process comprises the step of preparing the polymer compound.
3. The process for producing a mesostructured thin film according to claim 2, wherein the step of preparing the polymer compound is the step of forming a film of the polymer compound on a base plate.
4. The process for producing a mesostructured thin film according to claim 2, wherein the step of preparing the polymer compound is the step of forming a Langmuir-Blodgett film as the film of the polymer compound.
5. The process for producing a

mesostructured thin film according to claim 1, wherein the mesostructured thin film is formed on the polymer compound which has orientation.

5                    6.     The process for producing a mesostructured thin film according to claim 5, wherein the orientation of the polymer compound is uniaxial orientation.

10                    ~~5~~ 7.     The process for producing a mesostructured thin film according to claim 1, wherein the mesostructured thin film contains silicon.

15                    ~~6~~ 8.     The process for producing a ~~5~~ mesostructured thin film according to claim ~~7~~, wherein the mesostructured thin film contains silica.

20                    ~~7~~ 9.     The process for producing a mesostructured thin film according to claim 1, wherein the mesostructured thin film is formed by hydrolyzing a silicon alkoxide.

25                    ~~8~~ 10.     The process for producing a mesostructured thin film according to claim 1, wherein the mesostructured thin film is formed by hydrolysis reaction in the presence of a surfactant.

- 9 ~~11~~. The process for producing a 8  
mesostructured thin film according to claim ~~10~~, wherein  
the surfactant is a quaternary alkylammonium salt.
- 5 10 ~~12~~. The process for producing a 8  
mesostructured thin film according to claim ~~10~~, wherein  
the surfactant contains a polyethylene oxide as the  
hydrophilic group.
- 10 11 ~~13~~. The process for producing a 8  
mesostructured thin film according to claim ~~10~~, further  
comprising the step of removing the surfactant after  
forming the mesostructured thin film.
- 15 12 ~~14~~. The process for producing a 11  
mesostructured thin film according to claim ~~13~~, wherein  
the step of removing the surfactant is the step of  
baking the mesostructured thin film.
- 20 13 ~~15~~. The process for producing a 11  
mesostructured thin film according to claim ~~13~~, wherein  
the step of removing the surfactant is the step of  
removing the surfactant by solvent-extraction.
- 25 14 ~~16~~. The process for producing a  
mesostructured thin film according to claim 1, wherein  
the mesostructured thin film is formed by hydrolysis

reaction under an acidic condition.

15 ~~15~~ 17. The process for producing a  
mesostructured thin film according to claim 1, wherein  
the mesostructured thin film is formed by bringing a  
solution containing a material for the mesostructured  
thin film into contact with a surface of the polymer  
compound.

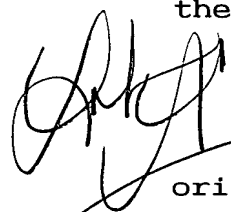
10 ~~16~~ 18. The process for producing a  
mesostructured thin film according to claim 1, wherein  
a surface of the polymer compound is subjected to  
rubbing treatment before the formation of the  
mesostructured thin film.

15 ~~17~~ 19. The process for producing a ~~16~~  
mesostructured thin film according to claim 18, wherein  
the rubbing treatment is conducted in a direction  
perpendicular to the mesochannels of the mesostructured  
20 thin film to be formed.

~~18~~ 20. The process for producing a  
mesostructured thin film according to claim 1, wherein  
the number of a sequence of adjacent methylene groups  
25 in the repeating unit of the polymer compound ranges  
from 2 to 20.

19 ~~21~~. The process for producing a  
mesostructured thin film according to claim 1, wherein  
the sequence of adjacent methylene groups in the  
repeating unit of the polymer compound is contained in  
5 the main chain of the polymer compound.

20 ~~22~~. The process for producing a  
mesostructured thin film according to claim 1, wherein  
the sequence of adjacent methylene groups in the  
10 repeating unit of the polymer compound is contained in  
the side chain of the polymer compound.

  
~~23. A mesostructured thin film having an  
oriented rod-like pore structure formed on a polymer  
15 compound, the polymer compound containing a sequence of  
two or more adjacent methylene groups in a molecular  
structure of the repeating unit of the polymer  
compound.~~

20 24. The mesostructured thin film according to  
claim 23, wherein the polymer compound is a surface of  
a Langmuir-Blodgett film of the polymer compound.

25 25. The mesostructured thin film according to  
claim 23, wherein the polymer compound has orientation.

~~26. The mesostructured thin film according to~~

claim 25, wherein the orientation of the polymer  
compound is uniaxial orientation.

27. The mesostructured thin film according to  
5 claim 23, wherein the mesostructured thin film contains  
silicon.

28. The mesostructured thin film according to  
10 claim 23, wherein the mesostructured thin film contains  
silica.

29. The mesostructured thin film according to  
15 claim 23, wherein the mesostructured thin film is  
formed by hydrolyzing a silicon alkoxide.

30. The mesostructured thin film according to  
20 claim 23, wherein the mesostructured thin film is  
formed by hydrolysis reaction in the presence of a  
surfactant.

31. The mesostructured thin film according to  
claim 23, wherein the mesostructured thin film has a  
hollow structure.

25 32. The mesostructured thin film according to  
claim 23, wherein the polymer compound is subjected to  
rubbing treatment before the formation of the

mesostructured thin film.

33. The mesostructured thin film according to  
claim 32, wherein the rubbing treatment is conducted in  
5 a direction perpendicular to mesochannels of the  
mesostructured thin film to be formed.

34. The mesostructured thin film according to  
claim 23, wherein the number of a sequence of adjacent  
10 methylene groups in the repeating unit of the polymer  
compound ranges from 2 to 20.

35. The mesostructured thin film according to  
claim 23, wherein the sequence of adjacent methylene  
15 groups in the repeating unit of the polymer compound is  
contained in the main chain of the polymer compound.

36. The mesostructured thin film according to  
claim 23, wherein the sequence of adjacent methylene  
20 groups in the repeating unit of the polymer compound is  
contained in the side chain of the polymer compound.

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C3



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